#### 4.5 Gunn diode

#### **Module:4 Microwave Sources**

Course: BECE305L – Antenna and Microwave Engineering

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Assistant Professor - SENSE

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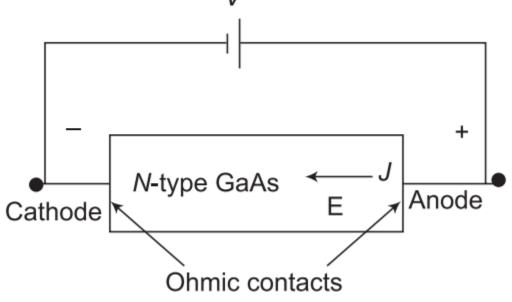


### **Module:4** Microwave Sources 5 hours

 Microwave frequencies and applications, Microwave Tubes: TWT, Klystron amplifier, Reflex, Klystron & Magnetron. Semiconductor Devices: Gunn diode, Tunnel diode, IMPATT – TRAPATT - BARITT diodes, PIN Diode.

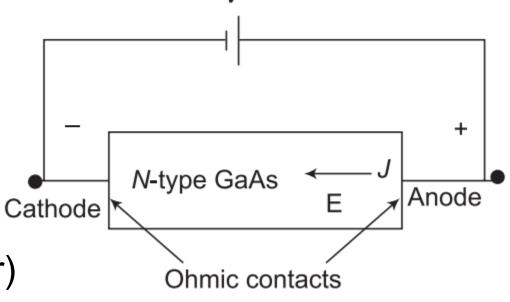
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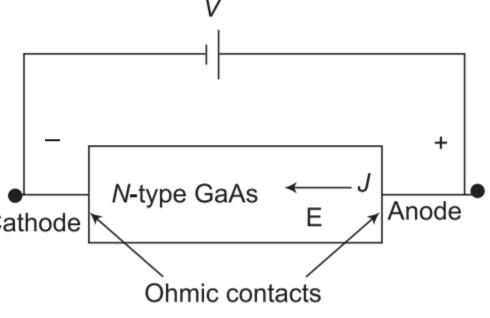
(TEDs)

GUNN diodes are also known as Transferred electron devices

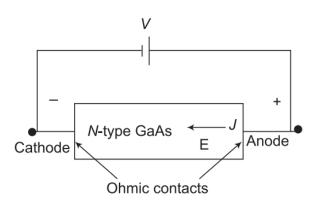
Low noise devices – named after JB Gunn

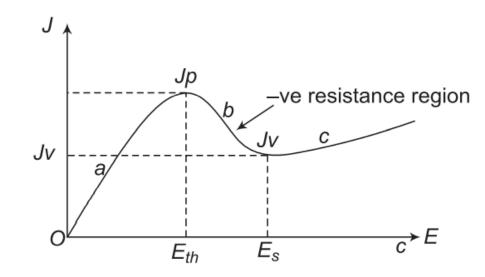
Periodic fluctuation of current passing through Cathode n-type gallium arsenide (n-GaAr) sample when the voltage difference exceeded a certain threshold.

- Similar observation in p-type GaAs, Indium phosphate (InP) and in semiconductors (CdTe, Tnsb, InAs, etc)
- Two metallic ends act as cathode and anode in single bulk semiconductor

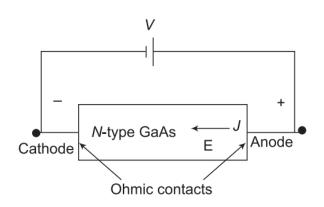


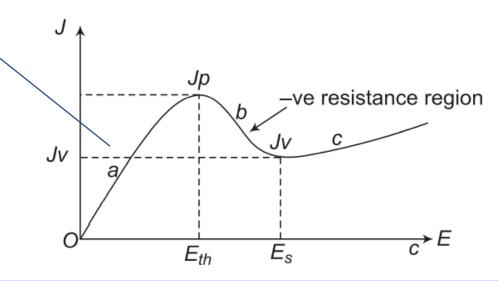
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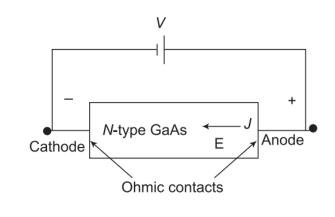


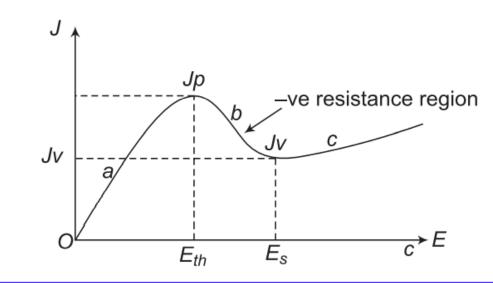
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- When  $E_{th} < E$  (slightly)  $< E_S$  sustaining value



Differential resistance  $\frac{dV}{dI}$  or  $\frac{dE}{dJ}$  is **negative** 



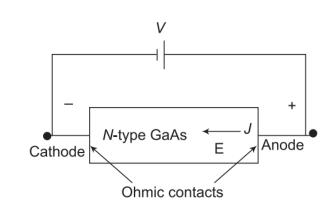


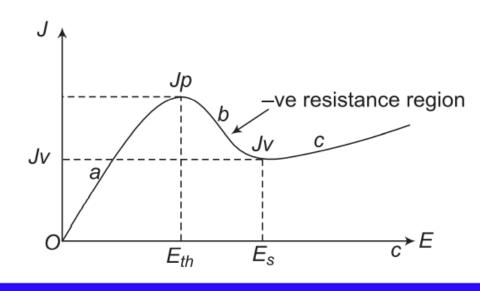


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- Negative slope of J E curve.

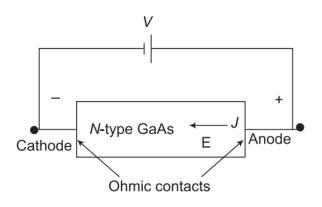
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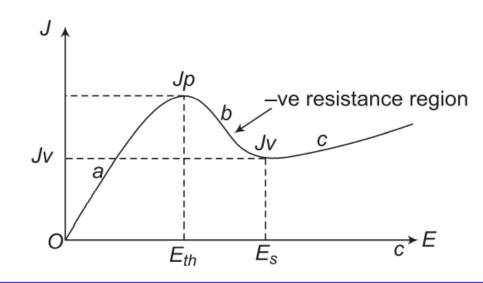
- This differential resistance is utilized for microwave gunn oscillators
- External resistance compensation is provided in the circuit to sustain oscillations





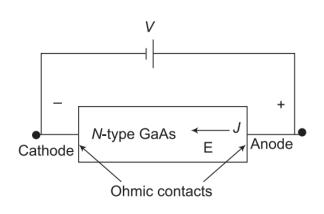
- Threshold value varies with type of material.
- n type GaAs, critical/ threshold value 3.2 kV/cm
- InP: 10.5 kV/cm





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 Applications: Low power microwave oscillator at microwave frequencies in transmitters and also as local oscillators in receiver front ends

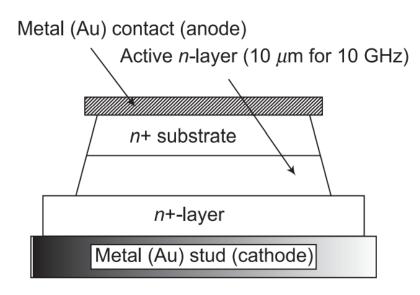


ve resistance region

 $E_s$ 

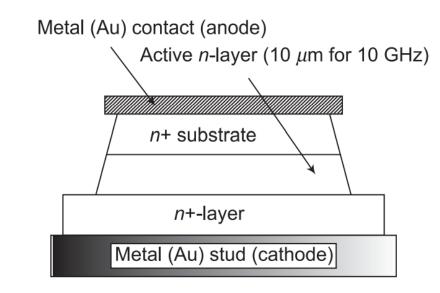
### 8.3 Construction details and electrical equivalent

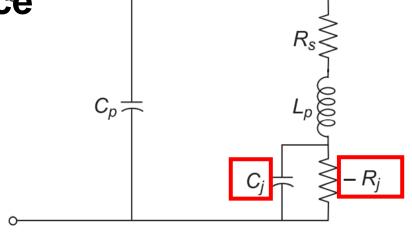
- Gold contacts as anode and cathode
- n type GaAs semiconductor
  Regions of high doping (n<sup>+</sup>)
- GaAs is poor conductor heat is generated.
  Hence generally a <u>Copper heat sink</u> is used.



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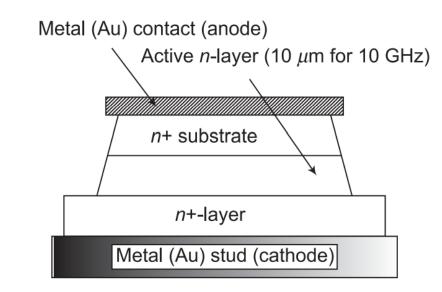
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- $C_j$ ,  $-R_j$ : Diode capacitance and resistance Negative resistance  $-5\Omega$  to  $-20\Omega$

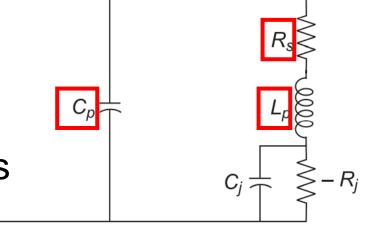




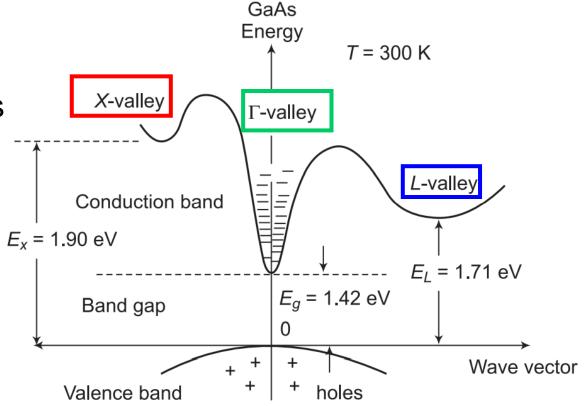
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- R<sub>s</sub> Total resistance due to ohmic contacts
- $C_p$ ,  $L_p$ : package capacitance and inductances



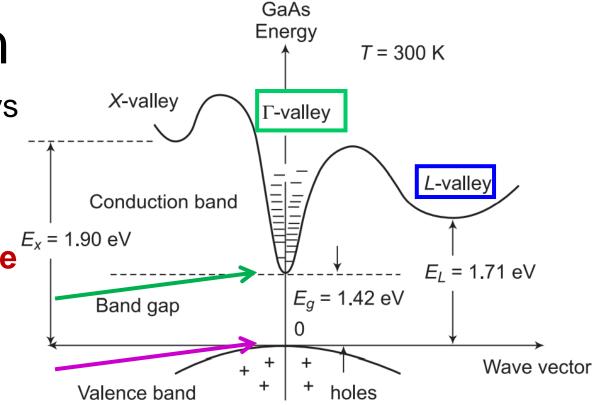


GaAs: Three conduction sub-bands or valleys
 (X, Γ, L)



Energy band diagram

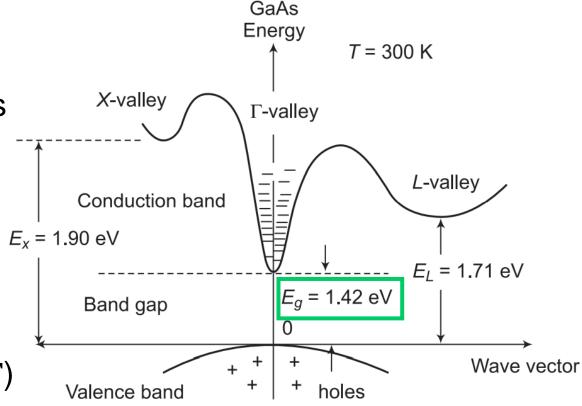
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- GaAs: <u>Superior electron mobility</u> with one maximum valence band and one minimum conduction band( $\Gamma$ ) occurring at same wave vector. (k =propagation constant =  $2\pi/\lambda$ ).



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Conductivity of the material  $\propto$  electron mobility  $\mu_n$ 



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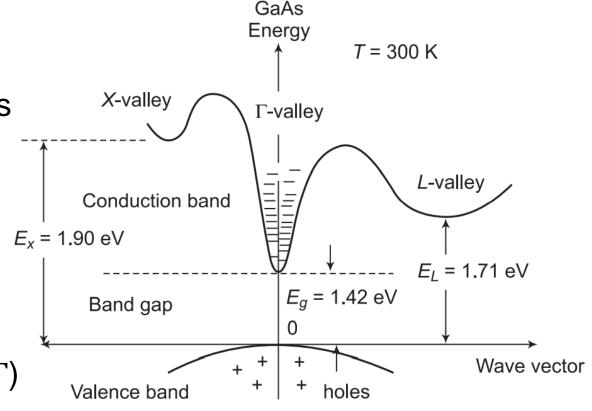
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#### Mobility of electron depends upon:

#### Concentration of impurity N in the semiconductor

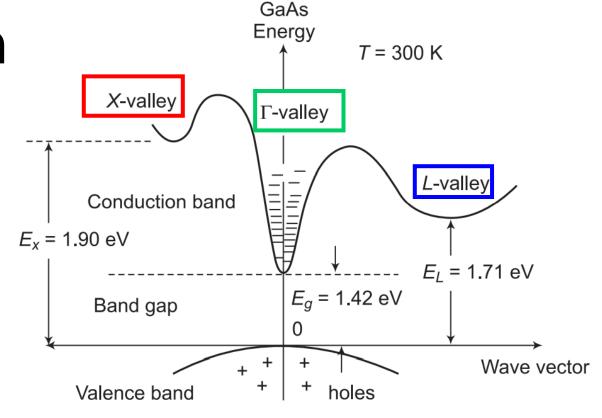
- Temperature T Kelvin
- Is inversely proportional to electron effective mass,  $m_n$



Energy band diagram

Current density is related to mobility by

$$J = en\mu_n E = e(n_X \mu_X + n_\Gamma \mu_\Gamma + n_L \mu_L)E$$

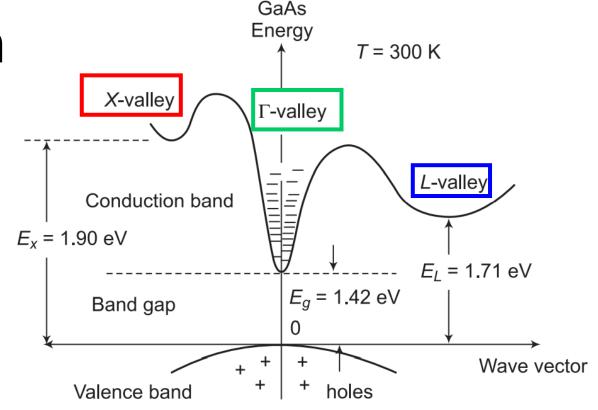


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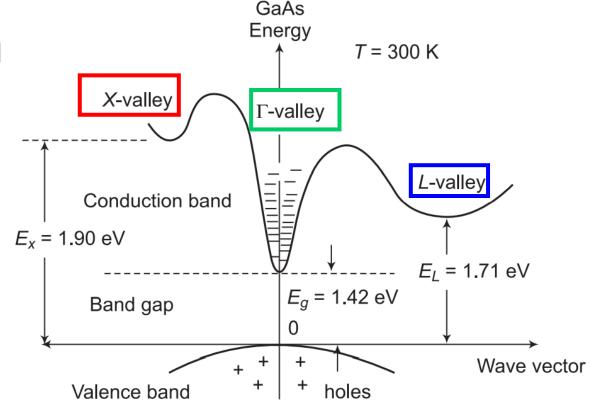


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- GaAs: Effective mass of these electrons in conduction band = 0.067 times mass of free electrons

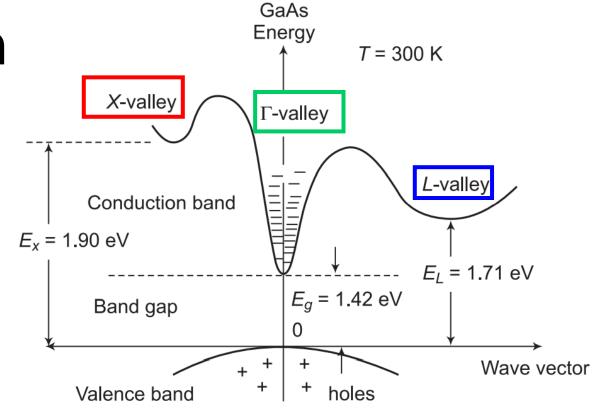


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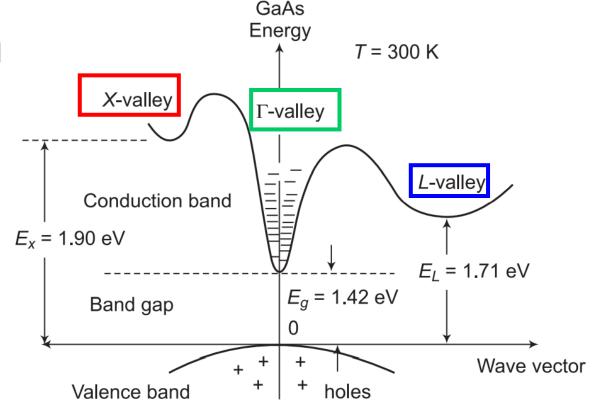
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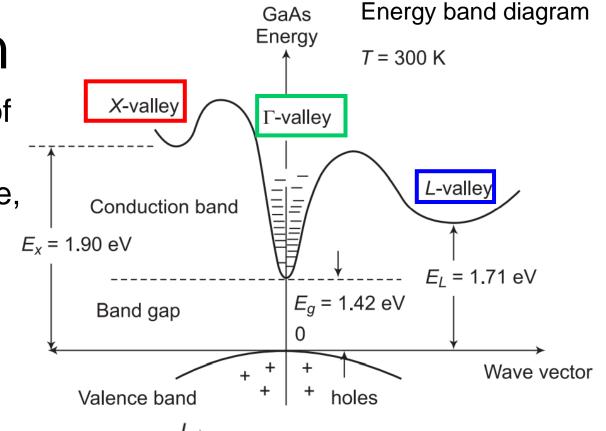
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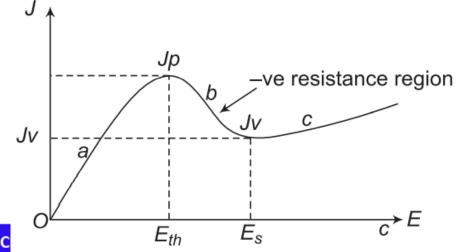
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Valleys X and L are wider with lower slopes, hence large effective mass and lower electron mobility.

• At room temperature 300K, most electrons of conduction band are in  $\Gamma$  valley (lowest)

• When Gunn diode is biased with a dc voltage, electric field *E* is established across it.

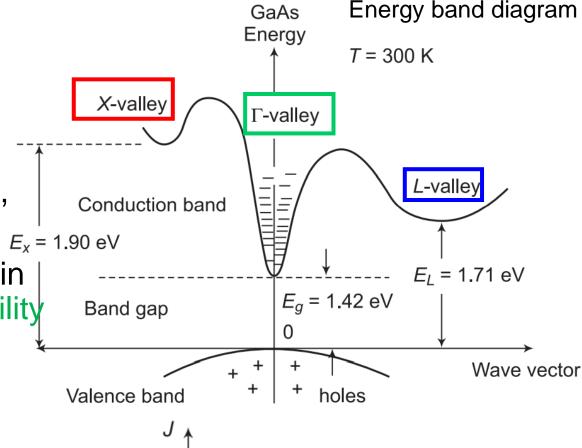


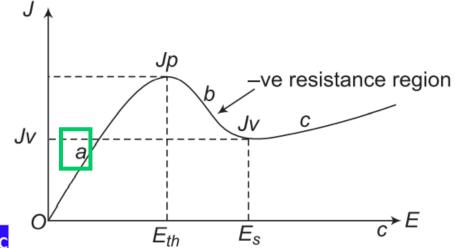


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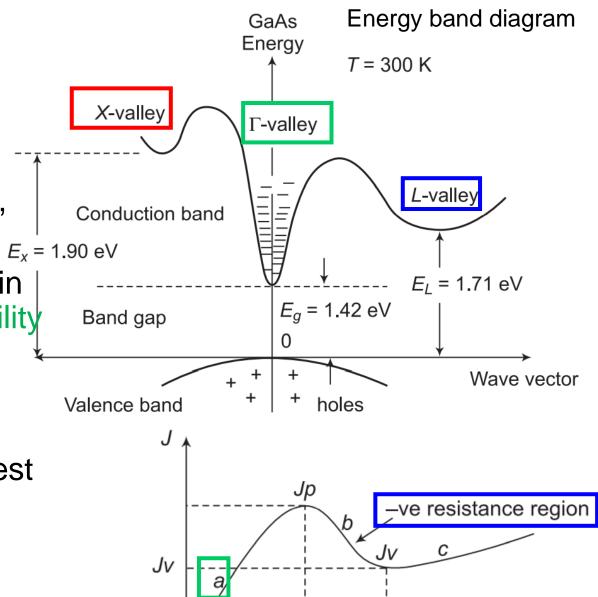


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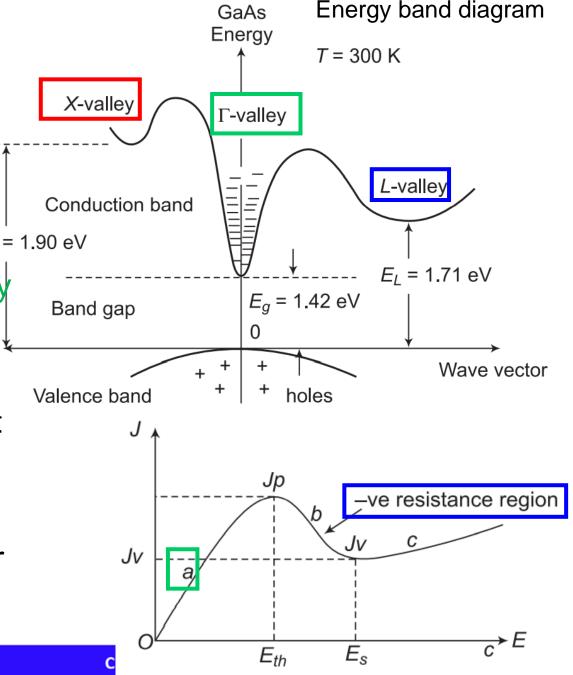
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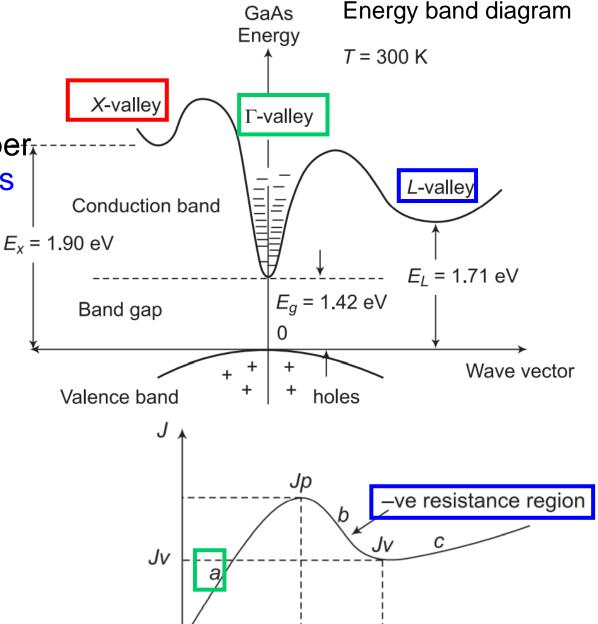
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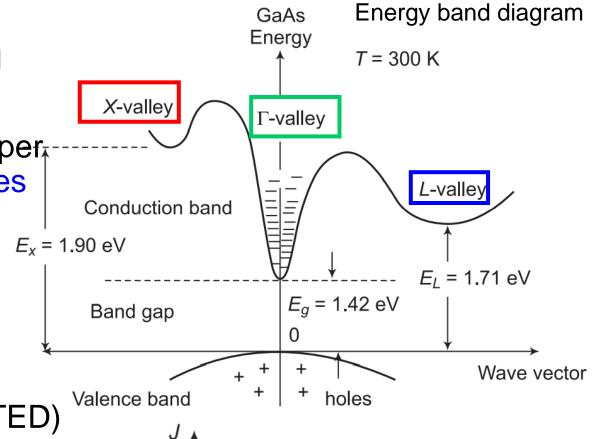


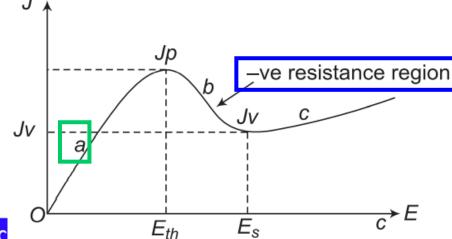
 $E_{th}$ 

 $E_s$ 

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• Decrease in current in region b: negative reistance:  $\frac{dJ}{dE}$  is negative, device behavior – differential negative resistance. Hence Gunn diodes are called Transfer Electron Device (TED)

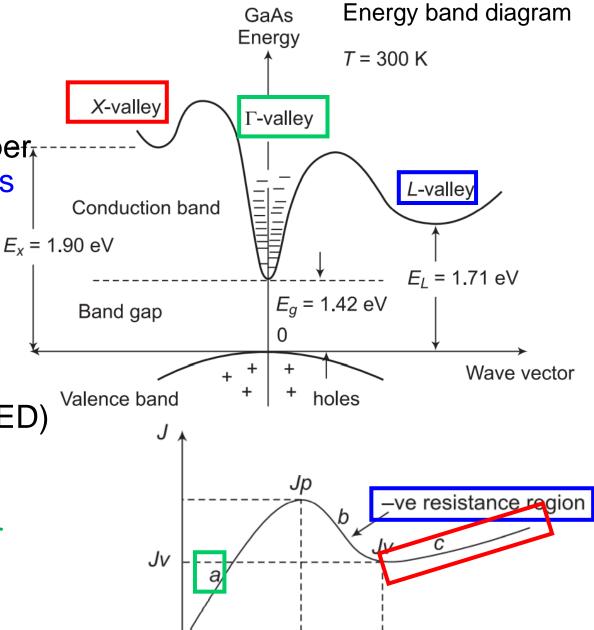




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• Beyond a sustaining field  $E = E_s$ , almost all conduction band electrons are in the upper valley: Upper valley mobility is less than lower valley.



GaAs

Energy

Γ-vallev

X-valley

Energy band diagram

L-valley

T = 300 K

### 8.4 Theory of operation

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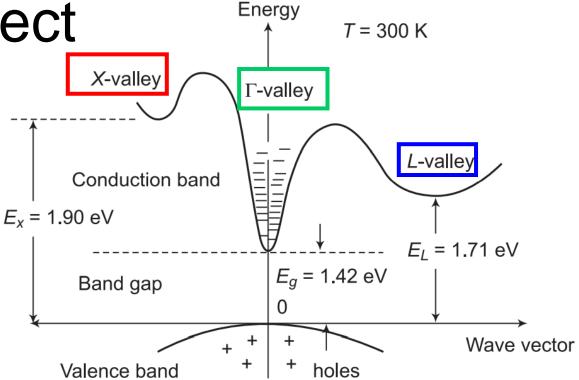
•  $E > E_s$ : net mobility of electrons – determined by Upper valley mobility: slope is positive J - E but lower than lower valley.

Conduction band  $E_x = 1.90 \text{ eV}$  $E_{l} = 1.71 \text{ eV}$  $E_q = 1.42 \text{ eV}$ Band gap Wave vector Valence band –ve resistance region

GaAs

8.5 Criteria for Gunn effect

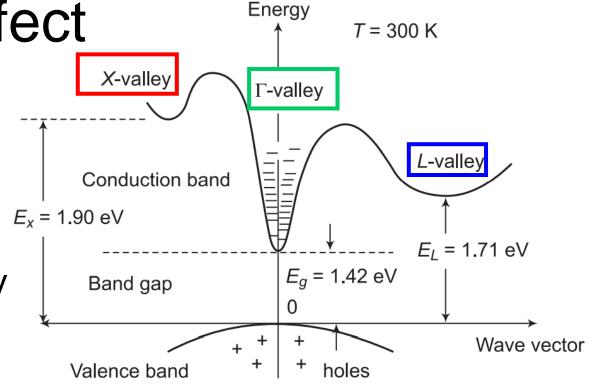
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GaAs

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- Band gap energy  $E_g \gg$  thermal energy kT = 0.026eV at room temperature

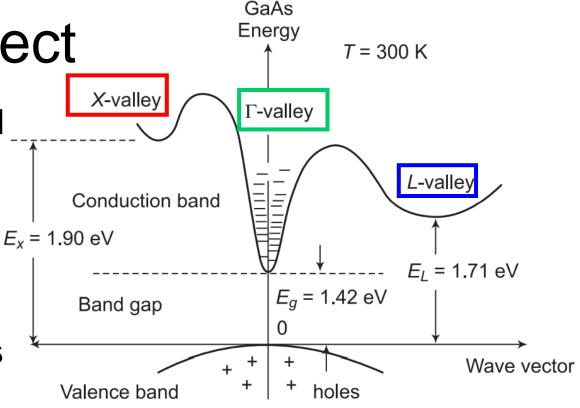


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- Band gap energy  $E_g \gg$  thermal energy kT = 0.026eV at room temperature
- Energy separation between two bands must be much lower than  $E_g$  but higher than kT

kT << Energy separation <<  $E_g$ 

 GaAs, InP (Indium Phosphate), CdTe (Cadmium telluride)

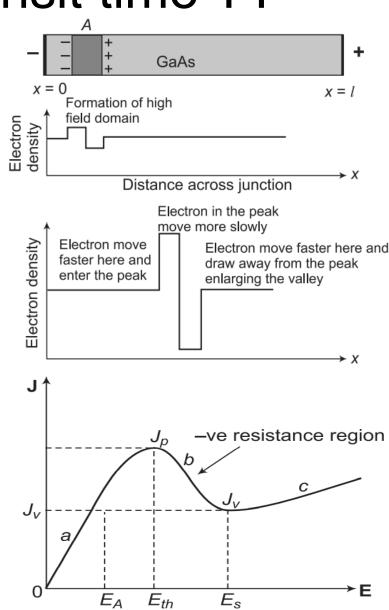


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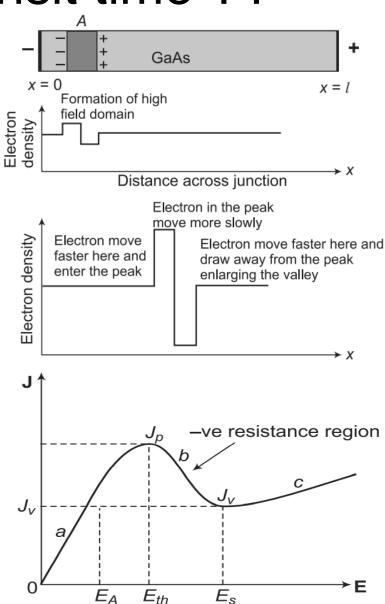
Properties	Si	<i>G</i> .	GaAs
Breakdown Field, V/m	approx. $3 \times 10^5$	approx. $1 \times 10^5$	approx. $4 \times 10^5$
Dielectric Constant	119	16.0	13 1
Effective Density of States in the Conduction Band, N/cm <sup>3</sup>	$2.8 \times 10^{19}$	$1.04 \times 10^{10}$	$4.7 \times 10^{17}$
Effective Density of States in the Valence Band, Nv/cm <sup>3</sup>	$1.04 \times 10^{18}$	$6.0 \times 10^{18}$	$7.0 \times 10^{18}$
Energy Gap at 300K (eV)	1.12	066	1.424
Intrinsic Carrier Concentration (cm <sup>3</sup> )	$1.45 \times 10^{10}$	$2.4 \times 10^{13}$	$1.79 \times 10^6$
Electron Mobility $\mu$ (cm <sup>2</sup> /V.s)	1500	3900	8500
Hole Mobility $\mu_p$ (cm <sup>2</sup> /V.s)	475	1900	400
Thermal Conductivity at 300 K (W/cm·°C)	15	0.6	0.46

# 8.6 Gunn mode of oscillations (Transit time TT mode)

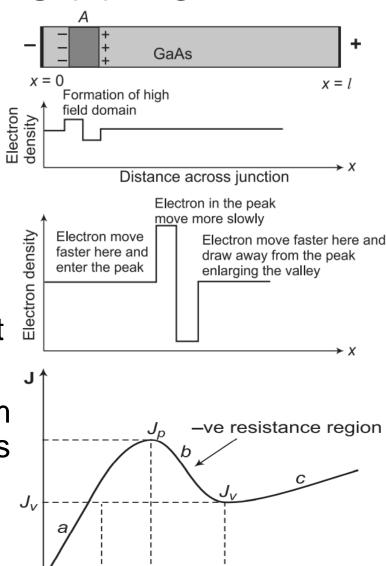
• In GaAs, in region b, the drift velocity decreases as there is decrease in mobility in upper valley (conduction band) with increase in electric field – Forms high field domain.



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- Assume at point A, excess –ve charge due to random noise/fluctuation on biasing/non-uniform doping. This creates electric field.
- Field towards left (cathode) is lower than field towards right (anode).

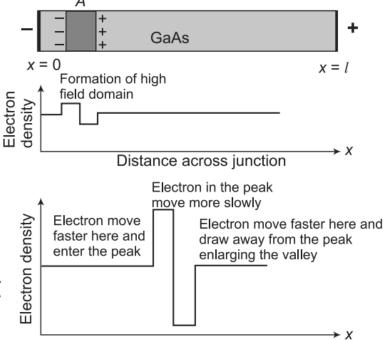


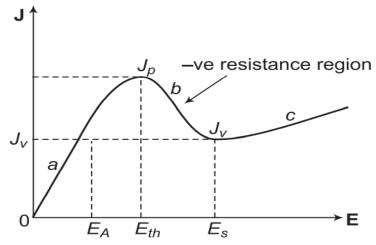
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- Field towards left (cathode) is lower than fiedld towards right (anode).
- When diode is biased at  $E_A(a)$ , carriers (current) flowing from cathode are larger than carriers from anode This increases excess —ve charge at A.



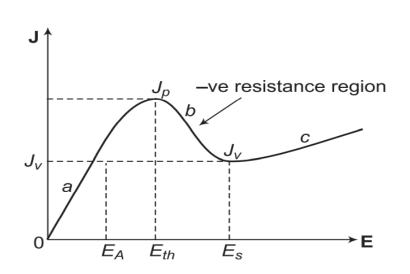
 $E_s$ 

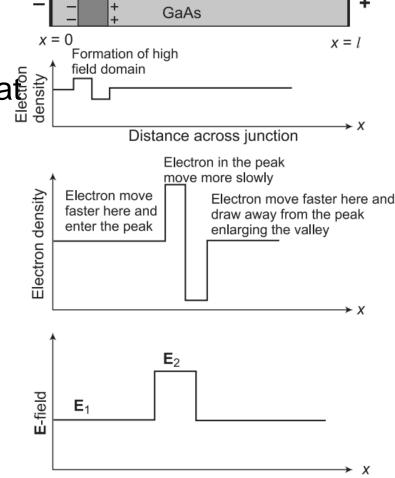
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- When diode is biased at  $E_A(a)$ , carriers (current) flowing from stathode are larger than carriers from anode This increases excess —ve charge at A.
- When RF noise reverses, field at left of A is lower than before, field towards right is greater than previous. – More space charge accumulation. – Fields accumulate and increase towards Eth



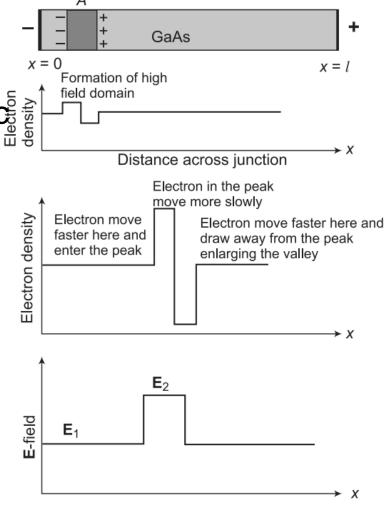


• This process continues until high and low fields both reach values outside the b region (-ve resistance region) at a and c (currents in both regions are equal now)

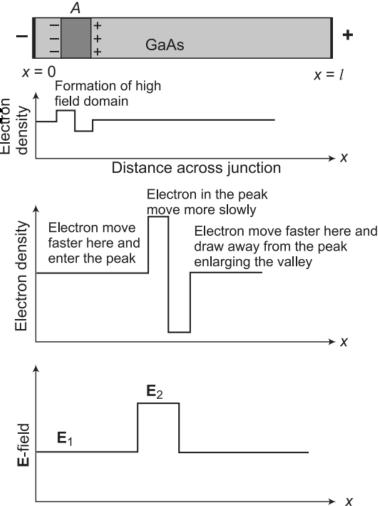




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- No further accumulation of Charge at A, and stable accumulation layer is formed.
- When the accumulation and depletion layers approach, they attract each other and pass through the diode in the form of domain.



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- No further accumulation of Charge at A, and stable accumulation layer is formed.
- When the accumulation and depletion layers approach, they attract each other and pass through the diode in the form of domain.
- Since  $V = -\int E dx$  across semiconductor remains constant, field inside the domain will be large. No additional domain forms until the existing domain disappears at Anode.
- Domain starts at cathode due to instability in carrier distribution.

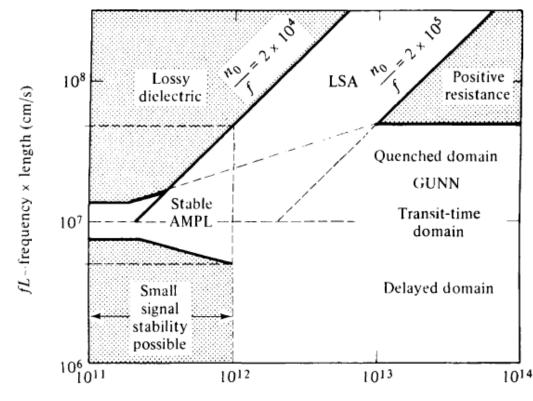


Formation of strong space charge instability depends on

- a) conditions of availability of enough charge in crystal (doping)
- b) sufficient length of the specimen should be available for building up of charges within the electron's transit time

For uniformly doped bulk diodes, four basic modes are:

- 1. Gunn Oscillation mode
- 2. Stable amplification mode
- 3. LSA oscillation mode
- 4. Bias circuit oscillation mode



length (cm/s)

#### 1. Gunn Oscillation mode:

Product of frequency and length  $fl = 10^7 cm/s$ 

Product of doping and length  $n_0 l > 10^{12}/cm^2$ 

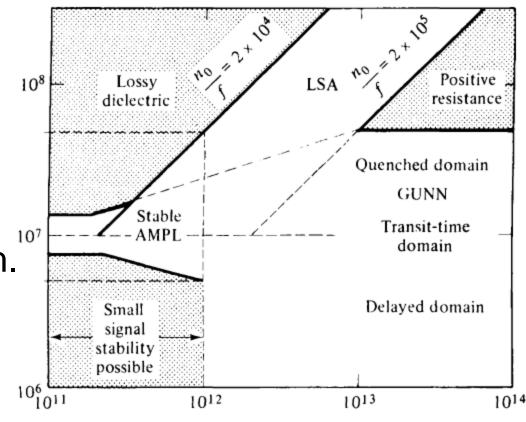
Unstable due to cyclic formation of

a) accumulation layer or

b) high field domain: in a circuit with low impedance  $(f_{oscillation}$ : near  $f_{intrinsic})$ 

For high Q cavity, when coupled properly to load, domain is quenched/delayed or both. Oscillation frequency:

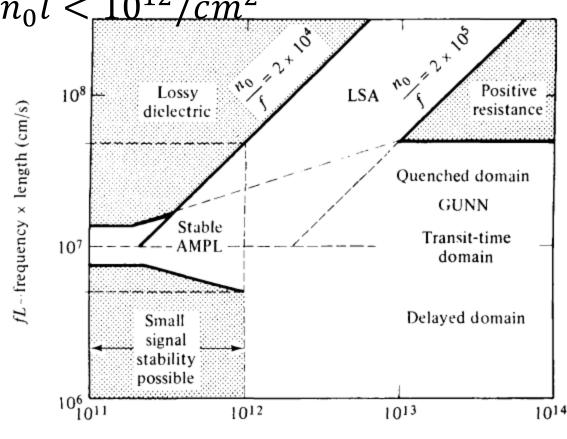
Depends on resonant frequency of the cavity



#### 2. Stable amplification mode:

Product of frequency and length  $fl = 10^7 cm/s$ 

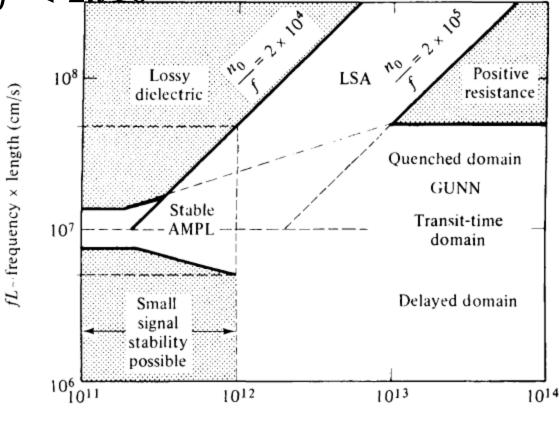
Product of doping and length  $10^{11}/cm^2 < n_0 l < 10^{12}/cm^2$ 



#### 3. LSA oscillation mode:

Product of frequency and length  $fl > 10^7 cm/s$  (greater than)

doping divided by frequency:  $2x10^4 < n_0/f < 2x10^5$ 

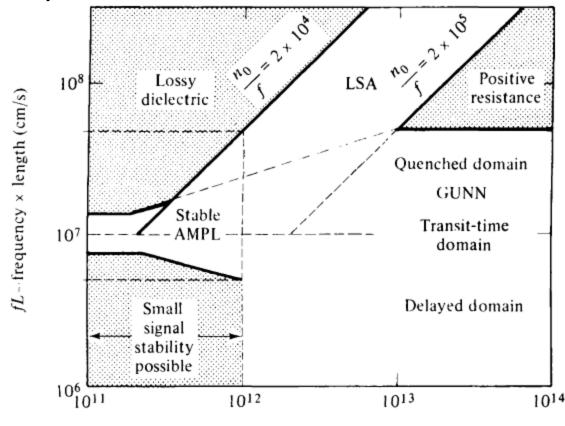


#### 4. Bias circuit oscillation mode:

When there is either Gunn or LSA oscillations Product of frequency and length  $fl \ll 10^6 cm/s$ 

When bulk diode is biased to threshold, average current suddenly drops and Gunn oscillations begins.

This results in oscillations in bias circuit 1 kHz to 100 MHz



## 8.8 LSA mode: Limited Spacecharge Accumulation mode

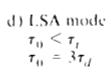
- Most of the operating domains are maintained in negative conductance state
- Space charge accumulation near cathode has time to collapse when signal voltage is maintained below threshold (maximum)
- Simplest state
- Uniformly doped semiconductor without any internal space-charge
- Internal electric field will be uniform without and proportional to applied field level

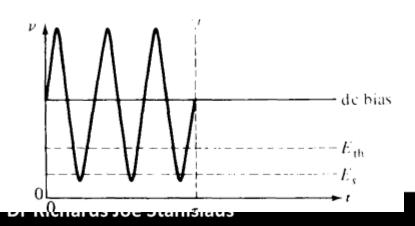
## 8.8 LSA mode: Limited Spacecharge Accumulation mode

#### 3. LSA oscillation mode:

Product of frequency and length  $fl > 10^7 cm/s$  (greater than)

doping times length:  $n_0L = 10^{12}/cm^2$ 





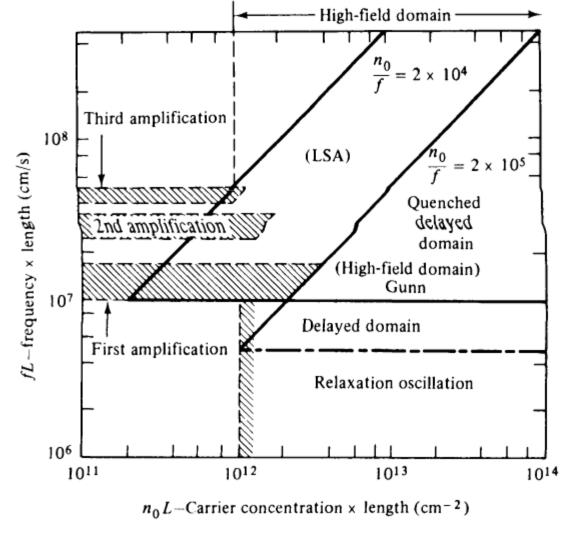
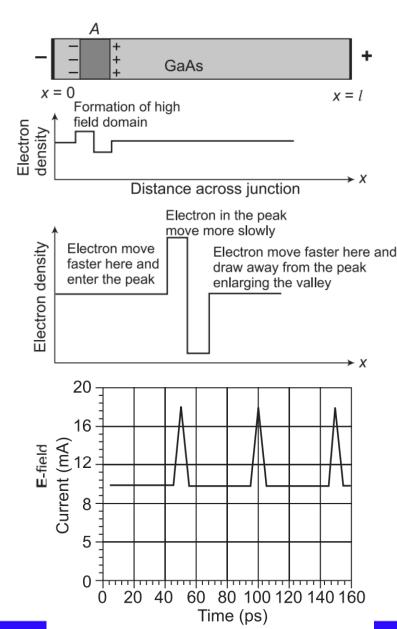


Figure 7-3-5 Mode chart. (After M. Uenohara [24]; reprinted by permission of McGraw-Hill Book Company.)

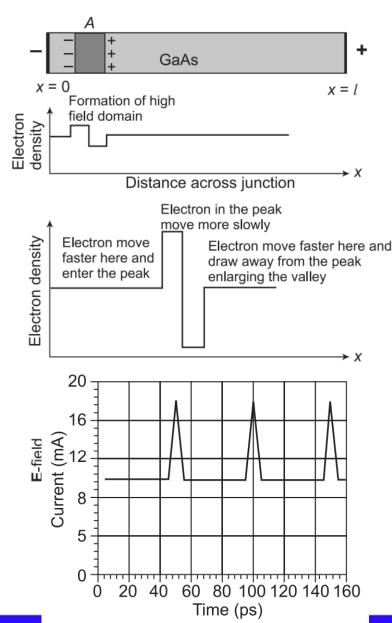
## 8.9 Microwave generation

- High field domain moves through the sample with uniform velocity  $v_d$  and gets collected at anode.
- New domain forms at cathode and again the process repeats as pulse.



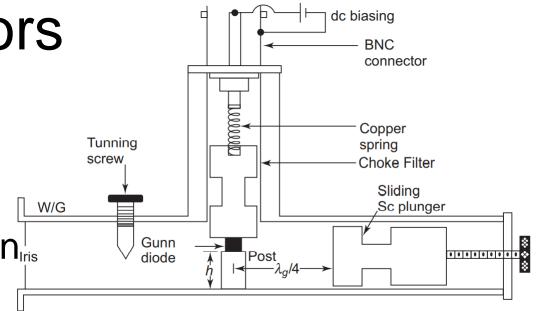
## 8.9 Microwave generation

- High field domain moves through the sample with uniform velocity  $v_d$  and gets collected at anode.
- New domain forms at cathode and again the process repeats as pulse.
- Pulse current output with intrinsic period T = transit time of domain
- $T = l_{eff}/v_d$  where  $l_{eff} \approx l$  length of sample and  $v_d$  is the drift velocity.

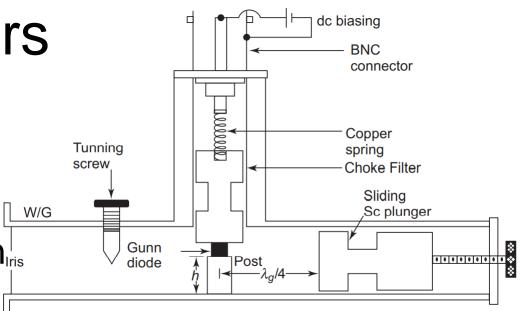


 Local oscillators in Radars, signal sources in lab

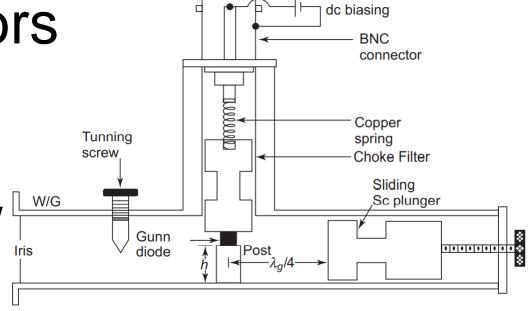
• Gunn diode is Mounted in waveguide cavity formed by short circuit termination at one end and by an iris at other end.



- Local oscillators in Radars, signal sources in lab
- Gunn diode is Mounted in waveguide cavity formed by short circuit termination at one end and by an iris at other end.
- Diode is mounted at center perpendicular to broadwall - at maximum electric field point (TE10).
- Intrinsic frequency  $f_0$  of oscillations depends on the drift velocity  $v_d$  due to the high field domain and effective length l.  $f_0 = v_d/l$

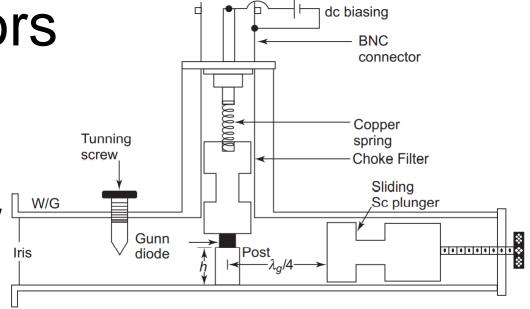


- GaAs:  $v_d = 10^5 m/s$
- Cavity is tuned by SC plunger
- For frequency fine-tuning, tuning screw is used before iris



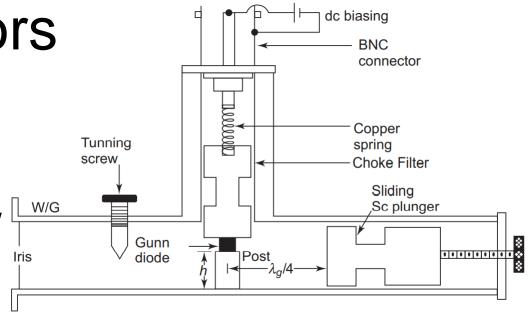
Degree of coupling - adjusted by selecting inductive iris.

- GaAs:  $v_d = 10^5 m/s$
- Cavity is tuned by SC plunger
- For frequency fine-tuning, tuning screw is used before iris
- Total resistive loading from cavity and external load >1.20 x Gunn device resistance  $-R_j$
- $-\frac{R_L R_j}{R_L R_j}$  will be negative



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- $-\frac{R_L R_j}{R_L R_j}$  will be negative
- Gun diode at metal post  $(<\lambda/4)$
- Post diameter 5mm at 10GHz



Degree of coupling - adjusted by selecting inductive iris.